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# ***Advances in X-Ray/EUV Optics and Components XVII***

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*Editors*

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# Contents

v *Conference Committee*

---

## REFLECTIVE OPTICS

---

- 12240 02 **The new ESRF compact multilayer coating system** [12240-2]
- 12240 03 **Diagnostics of KB mirrors misalignment using Zernike rectangular polynomials and neural networks** [12240-3]
- 12240 04 **Design of soft x-ray fluorescence microscopy beyond 100-nm spatial resolution with ultrashort Kirkpatrick-Baez mirror** [12240-4]
- 12240 05 **Multilayer coating design methods for a high-energy x-ray imaging optic with complex design requirements** [12240-5]

---

## SOURCES

---

- 12240 06 **Design and fabrication of multi-metal patterned target anodes for improved quality of hyperspectral x-ray radiography and computed tomography imaging systems** [12240-6]
- 12240 07 **Electric discharge relevant to pyroelectric spontaneous polarization inducing irreproducibility of pyroelectric x-ray generation** [12240-7]

---

## DIFFRACTIVE OPTICS

---

- 12240 08 **Fabrication of low blaze angle gratings by replication and plasma etch** [12240-13]
- 12240 09 **Measuring the x-ray flux from MEMS devices for timing applications** [12240-15]
- 12240 0A **Fabrication of ultra-thin single crystal diamond membrane by using laser ablation** [12240-17]

---

## ADAPTIVE OPTICS AND NEW APPLICATIONS

---

- 12240 0B **Magnetic smart material application to synchrotron x-ray optics: prospects and current progress** [12240-20]

---

## METROLOGY I

---

- 12240 0C **The ALS interferometric microscope upgraded for measurements with large x-ray optics and optical assemblies** [12240-23]
- 12240 0D **Reliability investigation of the instrument transfer function calibration technique based on binary pseudo-random array standards** [12240-25]
- 12240 0E **Towards super-resolution interference microscopy metrology of x-ray variable-line-spacing diffraction gratings: recent developments** [12240-26]
- 12240 0F **Dimensional and optical metrology of ultra-stable exactly-constrained KB mirror sets** [12240-27]

---

## METROLOGY II

---

- 12240 0G **Surface evaluation of high-precision monolithic mirror for soft x-ray focusing** [12240-28]
- 12240 0H **Advanced variable-resolution at-wavelength metrology with a coded-mask-based x-ray wavefront sensor** [12240-30]
- 12240 0I **Metrology of a coherent x-ray beam expander for advanced synchrotron sources** [12240-29]

---

## REFRACTIVE OPTICS

---

- 12240 0J **Hard x-ray wavefront engineering for aberration correction and beam shaping** [12240-10]
- 12240 0K **The large offset double-crystal monochromator for LCLS-HE upgrade** [12240-32]

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